

< *New market survey report* >

FO-WLP and RDL dielectric material

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Subjects and Focal points of survey

<Subjects of survey>

◆ FO-WLP (Fan-out Wafer Level Package):

- Chip-First type, RDL-First type

* But RDL-first type FO-WLP not using photolithography for semiconductor is not included.

◆ Dielectric material:

- Liquid type, Film type
- Photosensitive (positive/negative) and non-photosensitive

<Companies surveyed>

▼ FO-WLP assembler

- ASE, SPIL, TSMC, Amkor, STATS ChipPAC, Nanium, J Devices, Infineon, Freescale, Toshiba, Fujitsu laboratories, Others

▼ Dielectric material supplier

- Sumitomo Bakelite, HD Microsystems, Toray, Asahi Kasei E-Materials, Fujifilm EM, JSR, Asahi Glass, Shin-Etsu Chemical, Ajinomoto FT, Dow Chemical, Others

Focal points of survey

▼ FO-WLP

1. Main driver of Market growth

- By application IC: AP, BB/RF, PMIC, Substitute PKG of 2.5D IC,
- By needs: miniaturized wiring, low-profile PKG, cost reduction...

2. Technical issues for cost reduction and market expansion

- Shift from wafer based assembly to panel based assembly, and Enlargement of assembly work size
- Technologies and issues to realize panel based assembly and multi-RDL

▼ Dielectric material

1. Market growth of dielectric material

- By usage (Buffer coat, FC bump, RDL, Others)
- By form (liquid and film) of RDL materials for FO-WLP

2. Technical demands of RDL dielectric materials for FO-WLP:

- Required characteristics for FO-WLP and the assembly process

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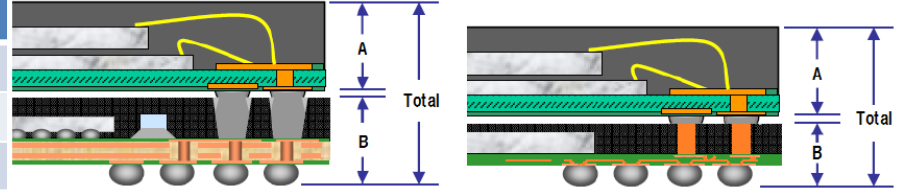
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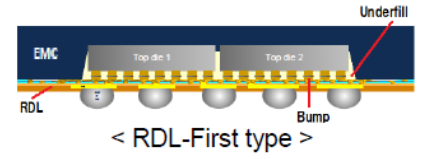
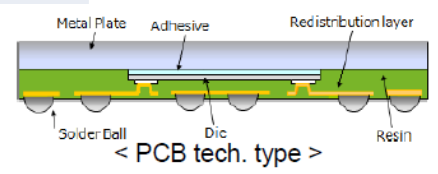
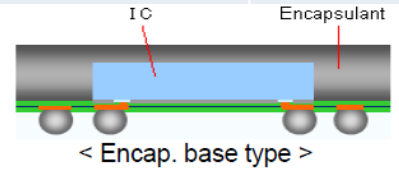
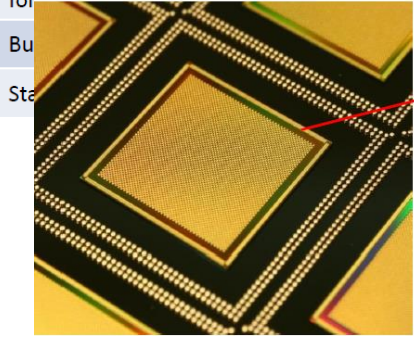
【Types of FO-WLP and the comparisons】

	Encapsulated base	PCB technology	RDL-First
Process type	Chip-First	Chip-First	RDL-First
Wafer/Panel	Wafer/Panel	Panel	Wafer/Panel
Work size (at present)	~ 300mm wafer	~ 400 x 500mm panel	300mm wafer

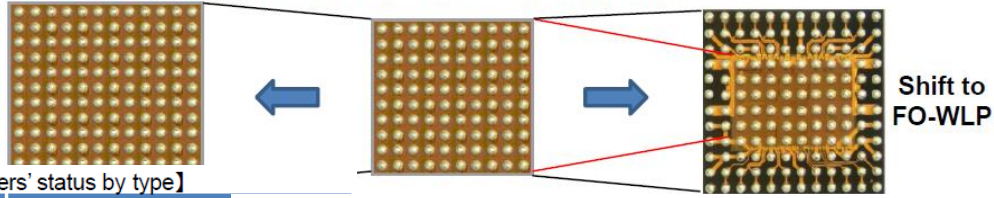
【Comparison of PKG height of AP by type (Left: FC-CSP based PoP, right: FO-WLP based PoP)】



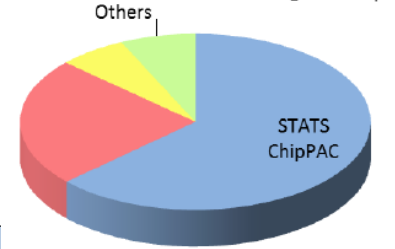
【Structure of TSMC's InFO-WLP】



【Technical comparison for the increase of IO number in WL-CSP】



【Multi chip PKG】



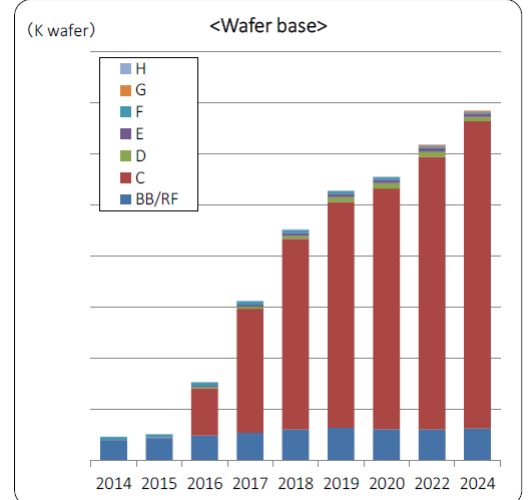
【List of FO-WLP assemblers' status by type】

Assembler	Name	Type of FO-W	
		Encap. Base*1	PCB tech.
Amkor Technology	WLFO	✓	
	SWIFT/SLIM		
ASE	aWLP		

【Market size forecast of FO-WLP by application and assembly work base】

		2014	2015	2016	2017	2018
BB/RF for Mobile	Wafer base	143				
	Panel base	0				
AP	Wafer base	0				
	Panel base	0				
	Wafer base	0				
		0				

【Market size forecast of the assembled FO-WLP on wafer base】



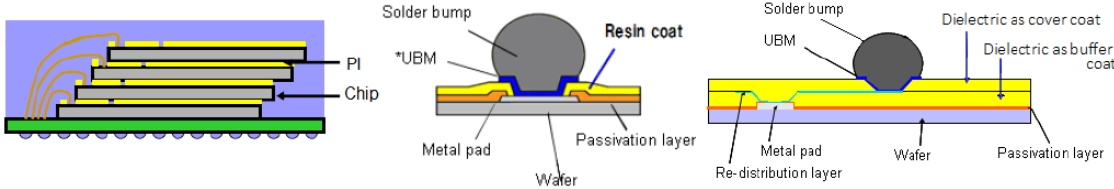
【Production status of FO-WLP assemblers by # of RDL in 2014 (in volume)】

	# of RDL layer				Total
	1-layer	2-layer	3-layer	4-layer & more	
STATS ChipPAC					

【Adoption possibility of FO-WLP type by application IC】

	IC type and the combination of ICs	The present PKG type	Encap. base		P
			Wafer	Panel	
	AP for Smartphone	PoP, FC-CSP			
	...	2.5D (+3D) PKG			
	...	FC-CSP, FO-WLP	✓	P	
	Total (K pieces)				

Samples of contents (from Chapter 3)



【 Types and usage of dielectric materials 】

Type of dielectric material		Usage
Photosensitivity	Polymeric material	
Photosensitive (Positive/Negative), Non-photosensitive	Polyimide (PI), Polybenzoxazole (PBO), Benzocyclobutene (BCB), Phenol, Epoxy, Others	Stress buffer coat, Passivation for bump, Interlayer dielectrics, Adhesive

【 Comparison of Spin-less coating methods 】

	Slit coater	Spray coater	Ink-jet coater
Coating speed	~ 200mm/s	40mm/s	10~100mm/s
Film thickness uniformity *	±3 ~ 5%	±5%	±3 ~ 5%
Material utilization ratio	approximately %	approximately %	approximately %

Coating speed	~ 200mm/s
Film thickness uniformity *	±3 ~ 5%
Material utilization ratio	approximately %
Range of the liquid viscosity that coaters can apply	
RDL dielectric material application to a panel	

【 Market size forecast of RDL dielectric materials for FO-WLP by form of material 】

		2014	2015	2016	2017	2018	2019
Liquid	Volume (t)						
	Amount (K USD)						
	Average (USD/kg)						
Film	Volume (m ²)						
	Amount (K USD)						
	Average (USD/m ²)						
Total	Amount (K USD)						

【 General status of manufacturers of dielectric material for semiconductor coat by type 】

	Form of material		Photosensitive/Non-photo			Polymeric type	
	Liquid	Film	Posi	Nega	Non-photo	PI/PBO	Others
Ajinomoto Fine-Techno	✓	✓					
	✓						
Asahi Kasei E-Materials	✓						
Dow Chemical	✓						
	✓						

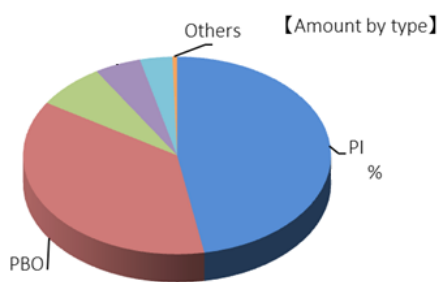
【 Required characteristics of RDL dielectric material for FI-WLP 】

	WL-CSP	FO-WLP	
Number of layers of RDL dielectric material	1 ~ 2-Layer	2-L and more (mainly 2~3)	· 1L abc · 2L for
Thickness of a dielectric	As buffer coat layer	Approximately 5μm	
	As cover coat layer	Approximately 8μm	
Chemical resistance			
...			

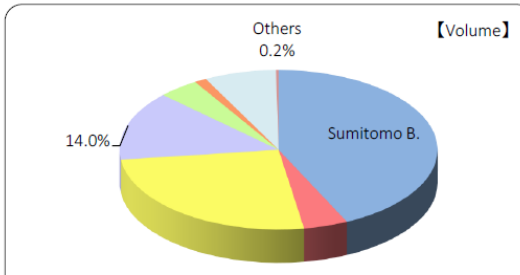
【 Sales status of dielectric material manufacturers by usage 】

	Volume (kg)		
	Buffer C.	FC bump	RDL
HD Microsystems			
Toray Industries			
Others			
Total			

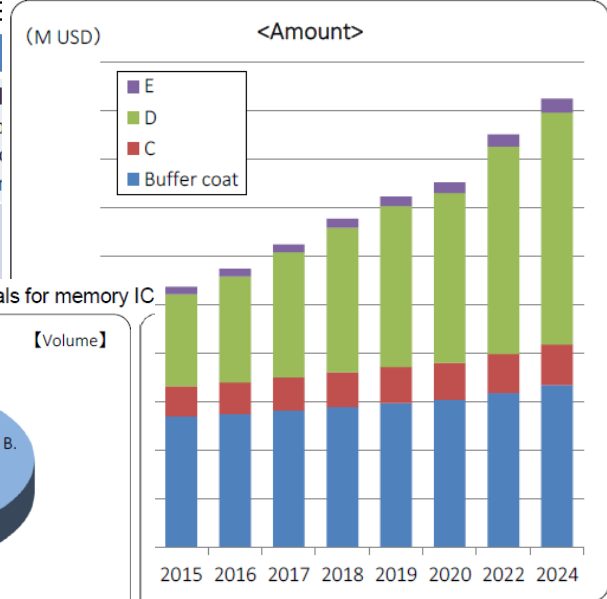
【 Market ratio of dielectric materials by type of polymer 】



【 Market share of buffer coat dielectric materials for memory IC 】



【 Market size forecast of liquid dielectric materials by usage 】



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